IN THE CLAIMS:

Please CANCEL claims 1-6, 17 and 26-29 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 10, 15, 21 and 24, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-6. (Canceled)

7. (Original) A projection exposure apparatus comprising:

a projection exposure mask which includes a first mask pattern for exposing a member to form a continuous pattern thereon and a second mask pattern for exposing the member to form a discontinuous pattern thereon, one of the first and second mask patterns being a reflecting type mask and the other mask pattern being a transmitting type mask pattern;

a projection system which projects light from the reflecting type mask pattern and light from the transmitting type mask pattern onto the member;

a first illumination system which irradiates light to the reflecting type mask pattern from one side of the projection exposure mask;

a second illumination system which irradiates light to the transmitting type mask pattern from the opposite side of the one side of the projection exposure mask; and

a substrate stage which moves the member in a direction substantially orthogonal to a projection light axis of the projection system.

8. (Original) The projection exposure apparatus according to claim 7, wherein the projection system combines light from the reflecting type mask pattern with light from the transmitting type mask pattern to project the combined light onto the member.

9. (Original) The projection exposure apparatus according to claim 7, wherein one of the first and second illumination systems irradiating light to the first mask pattern is of a continuous illumination type, and the other illumination system irradiating light to the second mask pattern is of an intermittent illumination type.

10. (Currently Amended) The projection exposure apparatus according to claim 7, wherein at least one of the first and second illumination systems irradiates light to the projection exposure mask in a linear or an arc slit-like shape.

11. (Original) The projection exposure apparatus according to claim 7, wherein the first illumination system irradiates light to the reflecting type mask pattern through the projection system.

12. (Original) The projection exposure apparatus according to claim 11, wherein the projection system includes a light splitting element, the light splitting element splitting an optical path of light irradiated to the reflecting type mask pattern from the first illumination system from an optical path of light reflected by the reflecting type mask pattern and projected onto the

member, and the light splitting element combining light from the reflecting type mask pattern with light from the transmitting type mask pattern.

13. (Original) The projection exposure apparatus according to claim 12, wherein the light splitting element is a polarization beam splitter, and the projection exposure apparatus further comprising a 1/4 wave plate disposed between the polarization beam splitter and the projection exposure mask.

14. (Original) The projection exposure apparatus according to claim 7, wherein the first illumination system irradiates the light to the projection exposure mask from outside the projection system, and the light is reflected by the reflecting type mask pattern and then irradiated by the projection system to the member.

15. (Currently Amended) The projection exposure apparatus according to claim 7, further comprising a parallel plate which is provided in the projection system and transmits light to be projected onto the member, the parallel plate being swung in a ~~forth direction and a~~ back and forth direction,

wherein the second mask pattern is irradiated with light in the swinging of the parallel plate in one direction of the ~~forth direction and a~~ back and forth direction.

16. (Original) The projection exposure apparatus according to claim 15, wherein the first mask pattern is irradiated with light during the swinging of the parallel plate.

17. (Canceled)

18. (Original) A method of projection exposure comprising the steps of:

a first step of preparing a projection exposure mask, the projection exposure mask having a first mask pattern for exposing a member to form a continuous pattern thereon and a second mask pattern for exposing the member to form a discontinuous pattern thereon, one of the first and second mask patterns being a reflecting type mask pattern and the other mask pattern being a transmitting type mask pattern;

a second step of projecting light from a projection system onto the member by using the projection exposure mask; and

a third step of moving the member in a direction substantially orthogonal to a projection light axis of the projection system,

wherein, at the second step, the reflecting type mask pattern is irradiated with light from one side of the projection exposure mask and the transmitting type mask pattern is irradiated with light from the opposite side of the one side of the projection exposure mask.

19. (Original) The method of projection exposure according to claim 18, wherein, at the second step, light from the reflecting type mask pattern is combined with light from the transmitting type mask pattern to project the combined light onto the member.

20. (Original) The method of projection exposure according to claim 18, wherein, at the second and third steps, the first mask pattern is continuously illuminated and the second mask pattern is intermittently illuminated.

21. (Currently Amended) The method of projection exposure according to claim 18, wherein, at the second step, the projection exposure mask is irradiated with light in a linear or an arc slit-like shape at the second step.

22. (Original) The method of projection exposure according to claim 18, wherein, at the second step, the reflecting type mask pattern is irradiated with light through the projection system.

23. (Original) The method of projection exposure according to claim 22, wherein, at the second step, the projection system separates an optical path of light irradiated to the reflecting mask pattern from an optical path of light reflected by the reflecting type mask pattern and projected onto the member, and combines light from the reflecting type mask pattern with light from the transmitting type mask pattern to project the combined light onto the member.

24. (Currently Amended) The method of projection exposure according to claim 18, wherein, at the second step, a parallel plate, which is provided in the projection system and transmits light to be projected onto the member, is swung in a ~~forth direction and a~~ back and forth direction.

25. (Original) The method of projection exposure according to claim 24, wherein, at the second step, the first mask pattern is irradiated with light during the swinging of the parallel plate.

26-29. (Canceled)